REMARKS/ARGUMENTS

Claims 4-9 and 11-17 are pending in this application. Support for the amendment to Claim 4 is found in Claims 1 and 2. Support for the amendment to Claim 7 is found in Claim 1. Support for Claim 11 is found in Tables 1-3 on page 33 of the specification. Support for Claims 12-17 is found in Claims 2-6 and the specification as originally filed. No new matter is added.

Applicants wish to thank Examiner Ashton for indicating that Claims 4, 7-9 are allowable. As amended herein, Claims 4 and 7 have been amended to include the limitations of the base claim. With respect to Claim 11, Applicants request that the Examiner reconsider the rejections in light of the amendment to Claim 11 and the following remarks.

The rejections of Claims 1,2, 3, 5, 6, 10 and 11 under 35 U.S.C. § 102(b) over U.S. 5,876,900 (U.S. '900) or U.S. patent no. 5,770,343 (U.S. '343) is obviated, in part, by amendment, and traversed, in part, for the reasons set forth below.

The chemically amplified resist composition claimed in Claim 11 is not described in either of the two cited patents because neither of the patents describe a chemically amplified resist that gives a line width difference between resist top and resist bottom of 4% or less in a resist pattern of 0.12 micron formed.

Applicants draw the Examiner's attention to page 33, Table 1-1 (reproduced below) composition 5 and 6 which contain the amine derivatives N-cyclohexylformamide and 1-Cyclohexyl-2-pyrrolidinone, respectively, in addition to the other components of the resist composition (described on page 31).

Table 1-1

Composition	Resin	Amine derivative
1	1	N-isopropylmethacrylamide
2	1	N-cyclohexylformamide
3	1	1-Cyclohexyl-2-pyrrolidinone
4	3	N-isopropylmethacrylamide
5	3	N-cyclohexylformamide
6	3	1-Cyclohexyl-2-pyrrolidinone
7	1	No addition
8	3	No addition
9	1	N-phenyldiethanolamine
10	3	2,6-Diisopropylaniline

As shown in Table 1-3 on the bottom of page 33 (reproduced below), Compositions 5 and 6 have a line width difference of 4% whereas other compositions had DD values greater than 4%.

Table 1-3

Composition	Sensitivity (mJ/cm^2)	Resolution (μm)	Resist shape	DD (%)
4	4.0	0.12	○	7
5	3.6	0.12	◎	4
6	4.5	0.12	◎	4
8	3.6	0.16	X	16
10	25.6	0.17	X	25

The prior art cited does not describe either of Compositions 5 or 6, for example. As a result, the prior art can not inherently describe a chemically amplified resist composition as claimed in Claim 11. Furthermore, as duly noted by the Examiner, the composition of Claim 4 is not described in the prior art references. Compositions 5 and 6 are within the Claim 4 definition of the amine derivative, which have the DD value of 4%. Therefore, Claim 11 cannot be anticipated by the disclosures in U.S. '900 or U.S. '343 and as a result, the Applicants request that the rejections be withdrawn.

Applicants also request that the application be passed onto issuance.

Respectfully submitted,

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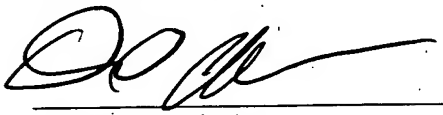

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